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<tr>
<td>Citation</td>
<td>IEEE Transactions on Magnetics, 53(11), 7942126; 2017</td>
</tr>
<tr>
<td>Issue Date</td>
<td>2017-11</td>
</tr>
<tr>
<td>URL</td>
<td><a href="http://hdl.handle.net/10069/37925">http://hdl.handle.net/10069/37925</a></td>
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Effect of ammonium chloride in plating baths on soft magnetic properties of electroplated Fe-Ni films

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We electroplated Fe-Ni films in plating baths with ammonium chloride (NH\textsubscript{4}Cl) and evaluated the magnetic properties of the films. The amount of NH\textsubscript{4}Cl did not affect the current efficiency of the plating process and the Fe content in the film. The obtained current efficiency of approximately 95\% is much higher than our previous study. The coercivity dramatically decreased with increasing NH\textsubscript{4}Cl from 0 to 15 g/L, and we obtained Fe\textsubscript{22}Ni\textsubscript{78} films with very low coercivity (10 A/m). The Cl\textsuperscript{-} concentration in the plating bath affected the coercivity, and we found that a plating bath with moderate low concentration of Cl\textsuperscript{-} is preferred for obtaining the Fe\textsubscript{22}Ni\textsubscript{78} films with low coercivity.

Index Terms— Soft magnetic material, Electroplating, Permalloy, Film

I. INTRODUCTION

Fluxgate sensors are one of attractive current sensors since they have high sensitivity and enable us to detect both dc and ac current. Focusing on these advantages, we have prepared a fluxgate sensor using an electroplated Fe-Ni-Co thick-film (≈ 20 μm) [1]. Owing to high economic viability of fabrication process, an electroplating is a hopeful method to obtain soft magnetic cores in fluxgate sensors, and some researchers also reported fluxgate sensors using electroplated soft magnetic alloys [2-3].

In general, Fe ions in a plating bath are not stable, and tend to be precipitated as hydroxide. Thus, a complexing agent is typically used for electroplating of Fe-group films. For the plating of Fe-group films, citrates are one of hopeful complexing agents [4-5], and chloride media are also often employed [6-7]. Osaka et al. have been reported Co-Fe-Ni films with high saturation magnetic flux density and low coercivity using ammonium chloride (NH\textsubscript{4}Cl) [8]. For electroplating of Ni films, the effect of NH\textsubscript{4}Cl on the crystal orientation has been reported [9]. As the orientation is one of factors to determine magnetic properties, we expected an improvement in soft magnetic properties of electroplated Fe-Ni films. In the present study, we electroplated Fe-Ni films prepared in plating baths with NH\textsubscript{4}Cl and evaluated the magnetic properties of the films.

II. EXPERIMENTAL PROCEDURES

A. Electroplating

We carried out an electroplating to obtain Fe-Ni films by using a direct current. The composition of the plating bath and the plating conditions are shown in Tables 1 and 2, respectively.

<table>
<thead>
<tr>
<th>Conditions</th>
<th>Values</th>
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<tbody>
<tr>
<td>Bath temperature</td>
<td>50°C</td>
</tr>
<tr>
<td>pH</td>
<td>Approx. 3.4 (Not adjusted)</td>
</tr>
<tr>
<td>Current density</td>
<td>200 mA/cm\textsuperscript{2}</td>
</tr>
<tr>
<td>Plating time</td>
<td>10 min</td>
</tr>
<tr>
<td>Anode (Ni)</td>
<td>5 mm × 15 mm</td>
</tr>
<tr>
<td>Substrate(Cu)</td>
<td>5 mm × 15 mm</td>
</tr>
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</table>

B. Measurements

The dc-hysteresis loops were measured with a B-H tracer (Riken Denshi BHS-40), and we obtained the coercivity values from the measured loops. As we fixed the current density and the plating time, all films showed almost the same thickness (Approx. 20 μm). The compositions and crystal structures of the films were analyzed by EDX (Hitachi High-technologies S-3000) and XRD (Miniflex 600-DX), respectively. The thicknesses of the as-plated Fe-Ni films were measured with a micrometer (Mitutoyo, CPM15-25MJ). The current efficiency was calculated from the actual weight of electroplated Fe-Ni films and the theoretical weight obtained by the Faraday’s law. All measurements were carried out for the Fe-Ni films in an as-plated state.
III. RESULTS AND DISCUSSION

Figure 1 shows Fe content and current efficiency as a function of NH$_4$Cl concentration. The concentrations of FeSO$_4$ and NaCl were fixed at 53 and 50 g/L, respectively. In our previous study for the citric acid, both the current efficiency and the Fe content decreases with increasing the concentration of the citric acid [5]. In contrast, both the current efficiency and the Fe content show almost constant values except for 0 g/L of NH$_4$Cl, indicating that we can vary the concentration of NH$_4$Cl without the change in the Fe content. The current efficiency of approximately 95% is much higher than those for our previous study (85%) [5] and other researcher’s ones (60 - 80%) [10-11].

![Fe content and current efficiency as a function of NH$_4$Cl concentration. The concentrations of FeSO$_4$ and NaCl were fixed at 53 and 50 g/L, respectively.](image1)

In our experimental conditions, the coercivity value for NaCl = 15 g/L shows much smaller than those for NaCl = 50 g/L and our previous study (broken line in Fig.2) [5].

As mentioned-above, we observed the slight increase of coercivity in higher NH$_4$Cl concentration region. The coercivity dramatically decreases with increase the NH$_4$Cl followed by a slight increase in higher NH$_4$Cl concentration region. Since addition of the NH$_4$Cl improves the surface condition as shown in the insets, we considered that the dramatic decrease in the coercivity is attributed to the improvement in the surface quality of the films. In our experimental conditions, the coercivity value for NaCl = 15 g/L shows much smaller than those for NaCl = 50 g/L and our previous study (broken line in Fig.2) [5].

![Coercivity as a function of NH$_4$Cl concentration. The insets indicate photographs and SEM images for the Fe$_{22}$Ni$_{78}$ films for 0 and 15 g/L of NH$_4$Cl.](image2)

Figure 2 shows coercivity of the Fe$_{22}$Ni$_{78}$ films as a function of NH$_4$Cl concentration. The results for the plating baths with 15 and 50 g/L of NaCl are shown in Fig.2. The insets indicate photographs and SEM images of the films for 0 and 15 g/L of NH$_4$Cl. The coercivity dramatically decreases with increase the NH$_4$Cl followed by a slight increase in higher NH$_4$Cl concentration region. Since addition of the NH$_4$Cl improves the surface condition as shown in the insets, we considered that the dramatic decrease in the coercivity is attributed to the improvement in the surface quality of the films. In our experimental conditions, the coercivity value for NaCl = 15 g/L shows much smaller than those for NaCl = 50 g/L and our previous study (broken line in Fig.2) [5].

![Coercivity of Fe$_{22}$Ni$_{78}$ films as a function of the Cl$^-$ concentration in the plating baths.](image3)

As mentioned-above, we observed the slight increase of coercivity in higher NH$_4$Cl concentration region. Figure 3 shows the coercivity of the Fe$_{22}$Ni$_{78}$ films as a function of the Cl$^-$ concentration in the plating baths. The Cl$^-$ concentration was calculated using concentrations of NH$_4$Cl and NaCl in the bath. Since the surfaces of the films were very rough in low Cl$^-$ concentration region (< 0.5 mol/L), we only show the results for the Fe$_{22}$Ni$_{78}$ films with smooth surfaces in Fig.3 in order to remove the effect of surface roughness on coercivity.

![XRD patterns of Fe$_{22}$Ni$_{78}$ films prepared in the plating bath with various Cl$^-$ concentrations.](image4)

In order to understand the change in the coercivity values shown in Fig.3, we carried out an XRD analysis. Figure 4 shows XRD patterns of Fe$_{22}$Ni$_{78}$ films prepared in the plating bath with various Cl$^-$ concentrations. The Cl$^-$ concentration was varied from 0.8 to 2.7 mol/L by the change in the concentrations of NaCl and NH$_4$Cl. We also show the result for the citric-acid-based bath [12] in Fig.4. Fe-Ni grains in the films for the NH$_4$Cl baths are oriented preferentially to the (111) plane compared with that for the citric acid bath, and this result agrees with that for Ni films [9]. Since the orientation slightly changes (111) to random with increasing the Cl$^-$ concentration, we considered that slight increase in the coercivity in higher Cl$^-$ concentration is attributed to the
changes in the grain orientation.

Fig.4 XRD patterns of Fe$_{22}$Ni$_{78}$ films prepared in the plating bath with various Cl$^-$ concentrations. The Cl$^-$ concentration was varied from 0.8 to 2.7 mol/L by the change in the concentrations of NaCl and NH$_4$Cl.

IV. CONCLUSIONS

In conclusion, we have investigated the effect of ammonium chloride in plating baths on soft magnetic properties of electroplated Fe-Ni films. The obtained results are summarized as follows:

(1) The plating process using ammonium chloride showed high current efficiency (> 95%), and NH$_4$Cl concentration did not affect Fe content of the films.

(2) Fe-Ni grains in the films for the NH$_4$Cl baths are oriented preferentially to the (111) plane.

(3) Plating baths with moderate low Cl$^-$ concentration is preferred for obtaining the Fe$_{22}$Ni$_{78}$ films with good soft magnetic properties.

ACKNOWLEDGMENT

Part of this work was carried out under the Cooperative Research Project Program of the Research Institute of Electrical Communication, Tohoku University.

REFERENCES


